

Nonlocal spin Hall effect and spin-orbit interaction in nonmagnetic metals

S. Takahashi^{*}, S. Maekawa*Institute for Materials Research, Tohoku University, Sendai, 980-8577, Japan
CREST, Japan Science and Technology Agency, Kawaguchi, 332-0012, Japan*

Received 12 June 2005; revised 13 June 2005; accepted 14 June 2005

Abstract

Spin Hall effect in a nonlocal spin-injection device is theoretically studied. Using a nonlocal spin-injection technique, a pure spin current is created in a nonmagnetic metal (N). The spin current flowing in N is deflected by spin-orbit scattering to induce the Hall current in the transverse direction and accumulate charge at the edges of N, yielding the spin-current induced Hall effect. We propose a method for extracting the spin-orbit coupling parameter in nonmagnetic metals via the nonlocal spin-injection technique. © 2008 Elsevier B.V. All rights reserved.

PACS: 72.25.-b; 72.25.Ba; 72.25.Mk; 85.75.Nn

Keywords: spin Hall effect; spin injection; spin current; nonlocal spin transport

There has been growing interest in spin transport in magnetic nanostructures, because of potential applications to spin electronic devices [1]. Recent experimental studies have demonstrated that the spin polarized carriers injected from a ferromagnet (F) into a nonmagnetic material (N) such as a normal metal [2,3,4,5] and superconductor [6,7] create a spin accumulation in N. In this paper, we consider a nonlocal spin-injection Hall device, and discuss the anomalous Hall effect (AHE) in the presence of spin current (or charge current) flowing in N, taking into account *side jump* and *skew scattering*.

The basic mechanism for AHE is the spin-orbit interaction in N, which causes a spin-asymmetry in the scattering of conduction electrons by impurities; up-spin electrons are preferentially scattered in one direction and down-spin electrons in the opposite direction. Spin injection techniques makes it possible to induce AHE in *nonmagnetic* conductors. When spin-polarized electrons are injected from F to N, these electrons moving in N are deflected by the spin-orbit scattering to induce the Hall current in the transverse direction and accumulate charge at the edges of N, yielding the spin-current induced spin Hall effect (SHE) [8,9,10].

Using the Boltzmann transport equations which incorporates the spin-asymmetric scattering of conduction electrons by nonmagnetic impurities in N within the Born approximation, we can derive the “total” spin and charge currents flowing in N [10,11]

$$\mathbf{J}_s = \mathbf{j}_s + \mathbf{j}_s^H, \quad \mathbf{J}_q = \mathbf{j}_q + \mathbf{j}_q^H. \quad (1)$$

where $\mathbf{j}_s = -(\sigma_N/e)\nabla\delta\mu_N$ and $\mathbf{j}_q = \sigma_N\mathbf{E}$ are the *longitudinal* spin and Ohmic currents, $\sigma_N = 2e^2N(0)D$ is the electrical conductivity, $\delta\mu_N = \frac{1}{2}(\mu_N^\uparrow - \mu_N^\downarrow)$ is the chemical potential shift, μ_N^σ is the chemical potential of electrons with spin σ , and D is the diffusion constant. The second terms in Eq. (1) are the transverse spin and charge Hall currents caused by spin-orbit scattering:

$$\mathbf{j}_s^H = \alpha_H [\hat{\mathbf{z}} \times \mathbf{j}_q] = \alpha_H \sigma_N (\hat{\mathbf{z}} \times \mathbf{E}), \quad (2)$$

$$\mathbf{j}_q^H = \alpha_H [\hat{\mathbf{z}} \times \mathbf{j}_s] = -\frac{\alpha_H \sigma_N}{e} (\hat{\mathbf{z}} \times \nabla \delta\mu_N), \quad (3)$$

with $\alpha_H = \alpha_H^{\text{SJ}} + \alpha_H^{\text{SS}}$, where $\alpha_H^{\text{SJ}} = \hbar\bar{\eta}_{\text{so}}/(3mD)$ is the side jump (SJ) contribution, and $\alpha_H^{\text{SS}} = (2\pi/3)\bar{\eta}_{\text{so}}N(0)V_{\text{imp}}$ is the skew scattering (SS) contribution, $\bar{\eta}_{\text{so}} = k_F^2\eta_{\text{so}}$ is the dimensionless spin-orbit coupling parameter, k_F is the Fermi momentum, and V_{imp} is the impurity potential.

Equations (2) and (3) indicate that the spin current \mathbf{j}_s induces the transverse *charge* current (charge Hall current) \mathbf{j}_q^H , whereas the charge current \mathbf{j}_q induces the transverse *spin* current (spin Hall current) \mathbf{j}_s^H . Equation (1) is expressed in the matrix forms

$$\begin{bmatrix} J_{q,x} \\ J_{s,y} \end{bmatrix} = \begin{bmatrix} \sigma_{xx} & -\sigma_{xy} \\ \sigma_{xy} & \sigma_{xx} \end{bmatrix} \begin{bmatrix} E_x \\ -\nabla_y \delta\mu_N/e \end{bmatrix}, \quad (4)$$

$$\begin{bmatrix} J_{s,x} \\ J_{q,y} \end{bmatrix} = \begin{bmatrix} \sigma_{xx} & -\sigma_{xy} \\ \sigma_{xy} & \sigma_{xx} \end{bmatrix} \begin{bmatrix} -\nabla_x \delta\mu_N/e \\ E_y \end{bmatrix}, \quad (5)$$

^{*} Corresponding author. S. Takahashi
Email address: takahasi@imr.tohoku.ac.jp (S. Takahashi).

where $\sigma_{xx} = \sigma_N$ is the longitudinal conductivity and σ_{xy} is the Hall conductivity contributed from SJ and SS: $\sigma_{xy} = (\alpha_H^{SJ} + \alpha_H^{SS})\sigma_N = \sigma_{xy}^{SJ} + \sigma_{xy}^{SS}$ with

$$\sigma_{xy}^{SJ} = \frac{e^2}{\hbar} \eta_{so} n_e, \quad \sigma_{xy}^{SS} = \alpha_H^{SJ} \frac{n_e}{n_{imp}} [N(0)V_{imp}]^{-1}, \quad (6)$$

where n_e is the carrier (electron) density and n_{imp} is the impurity concentration. Note that σ_{xy}^{SJ} is independent of impurity concentration n_{imp} .

The ratio of the SJ and SS Hall contributions is

$$\frac{\sigma_{xy}^{SJ}}{\sigma_{xy}^{SS}} = 2 \frac{n_{imp}}{n_e} N(0)V_{imp} = \frac{3}{4\pi} \frac{\hbar}{\epsilon_F \tau_{imp}} \frac{1}{N(0)V_{imp}}, \quad (7)$$

where τ_{imp} is the momentum scattering time and ϵ_F is the Fermi energy. In ordinary non-magnetic metals, the ratio is very small because $n_{imp} \ll n_e$ and $N(0)V_{imp} \sim 1$, so that SS gives the dominant contribution to SHE. However, in very dirty metals or in low-carrier materials such as doped semiconductors with $n_{imp} \sim n_e$, the SJ conductivity is comparable to or even larger than the SS conductivity in SHE.

In the following, we consider a spin-injection Hall device shown in Fig. 1, and concentrate on the spin-current induced SHE. The magnetization of F electrode points to the z direction. When the current I is sent from F to the left side of N, the spin-polarized electrons are injected to create a pure spin current \mathbf{j}_s in N on the right side, where the total charge current is expressed as

$$\mathbf{J}_q = -(\alpha_H \sigma_N / e) (\hat{\mathbf{z}} \times \nabla \delta \mu_N) + \sigma_N \mathbf{E}. \quad (8)$$

where the first term is the Hall current induced by \mathbf{j}_s , the second term is the Ohmic current induced by surface charge, and $\alpha_H \sim \bar{\eta}_{so} N(0)V_{imp}$ (skew scattering). In the open circuit condition in the transverse direction, where J_q^y vanishes, the nonlocal Hall resistance $R_H = V_H/I$ becomes

$$R_H = \frac{1}{2} \alpha_H P_T (\rho_N / d_N) e^{-L/l_N}, \quad (9)$$

in the case of tunnel junction, where P_T is the tunneling spin polarization, ρ_N is the resistivity, l_N is the spin-diffusion length, and d_N is the thickness of N. In the case of metallic-contact junction

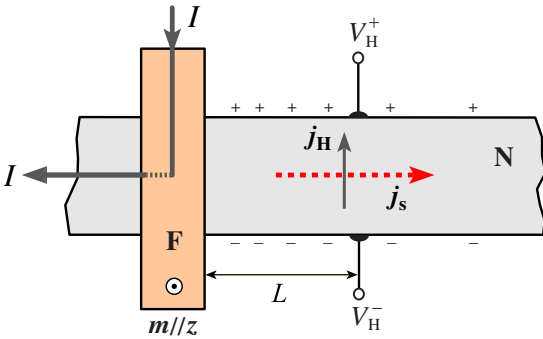


Fig. 1. Spin injection Hall device (top view). The magnetic moment of F is aligned perpendicular to the plane. The spin-current induced Hall voltage $V_H = V_H^+ - V_H^-$ is induced in the transverse direction by injection of pure spin current \mathbf{j}_s .

Table 1
Spin-orbit coupling parameter $\bar{\eta}_{so}$ of Cu, Al, and Ag.

	l_N (nm)	ρ_N ($\mu\Omega\text{cm}$)	τ_{imp}/τ_{sf}	$\bar{\eta}_{so}$
Cu ^a	1000	1.43	0.70×10^{-3}	0.040
Cu ^b	1500	1.00	0.64×10^{-3}	0.037
Cu ^c	546	3.44	0.41×10^{-3}	0.030
Al ^d	650	5.90	0.36×10^{-4}	0.009
Ag ^e	195	3.50	0.50×10^{-2}	0.110

^aRef. [2], ^bRef. [3], ^cRef. [4], ^dRef. [2], ^eRef. [5].

$$R_H = \frac{1}{2} \alpha_H \frac{p_F}{1 - p_F^2} (\rho_N / d_N) \frac{R_F}{R_N} \sinh^{-1}(L/l_N), \quad (10)$$

where p_F is the spin polarization of F, R_N and R_F are the spin resistances of the N and F electrodes: $R_N = (\rho_N l_N)/A_N$ and $R_F = (\rho_F l_F)/A_J$ with A_N the cross-sectional area of N and A_J the contact area between N and F. Usually, R_N is one or two orders of magnitude larger than R_F [12]. Recently, the spin-current induced AHE have been measured using spin injection techniques [13,14].

It is worthwhile to make the product $\rho_N l_N$, which is related to the spin-orbit coupling parameter $\bar{\eta}_{so}$ as

$$\rho_N l_N = \frac{\sqrt{3}\pi}{2} \frac{R_K}{k_F^2} \sqrt{\frac{\tau_{sf}}{\tau_{imp}}} = \frac{3\sqrt{3}\pi}{4} \frac{R_K}{k_F^2} \frac{1}{\bar{\eta}_{so}}, \quad (11)$$

where $R_K = \hbar/e^2 \sim 25.8 \text{ k}\Omega$ and τ_{sf} is the spin-flip scattering time. The formula (11) provides a method for extracting the physical parameters of spin-orbit scattering in nonmagnetic metals. Using experimental data of ρ_N and l_N in Eq. (11), we obtain the value of the spin-orbit coupling parameter $\bar{\eta}_{so} = 0.01\text{--}0.04$ in Cu, Al, and Ag as listed in Table 1. Therefore, Eqs. (9) and (10) yields R_H of the order of $0.1\text{--}1 \text{ m}\Omega$, indicating that the spin-current induced SHE is observable by using nonlocal spin-injection Hall devices.

This work was supported by the NAREGI Nanoscience Project, Japan.

References

- [1] *Concept in Spin Electronics*, edited by S. Maekawa (Oxford Univ Press, 2006).
- [2] F. J. Jedema *et al.*, Nature (London) **410** (2001) 345; **416** (2002) 713; Phys. Rev. B **67** (2003) 085319.
- [3] T. Kimura *et al.*, Appl. Phys. Lett. **85**, 3795 (2004); Phys. Rev. B **72** (2005) 014461; Phys. Rev. Lett. **96** (2006) 037201.
- [4] S. Garzon *et al.*, Phys. Rev. Lett. **94** (2005) 176601.
- [5] R. Godfrey and M. Johnson, Phys. Rev. Lett. **96** (2006) 136601.
- [6] M. Urech *et al.*, J. Appl. Phys. **99**, 08M513 (2006).
- [7] K. Miura *et al.*, Jpn. J. Appl. Phys. **45**, 2888 (2006).
- [8] J. E. Hirsch, Phys. Rev. Lett. **83** (1999) 1834.
- [9] S. Zhang, Phys. Rev. Lett. **85** (2001) 393.
- [10] S. Takahashi and S. Maekawa, Phys. Rev. Lett. **88** (2002) 116601.
- [11] S. Takahashi *et al.*, Chapter 8 in *Concept in Spin Electronics*, edited by S. Maekawa (Oxford Univ Press, 2006).
- [12] S. Takahashi and S. Maekawa, Phys. Rev. B **67** (2003) 052409.
- [13] T. Kimura *et al.*, J. Magn. Magn. Mater. **272-276** (2004) e1333.
- [14] H. Saitoh *et al.*, Appl. Phys. Lett. **88** (2006) 182509.